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**RESPONSE UNDER 37 C.F.R. §1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1792**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Kwang Su Choe, et al.

Examiner: Marianne L. Padgett

Serial No.: 10/674,647

Art Unit: 1792

Filed: September 30, 2003

Docket: YOR920030293US1 (16818)

For: THIN BURIED OXIDES BY LOW-DOSE
OXYGEN IMPLANTATION INTO MODIFIED
SILICON

Dated: November 16, 2009

Confirmation No: 4796

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

RESPONSE UNDER 37 C.F.R. § 1.116

Sir:

In response to the Final Office Action dated September 15, 2009, Applicants respectfully request that the following amendments and remarks be considered for entry as a matter of record in the above referenced application.

CERTIFICATE OF ELECTRONIC FILING

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on November 16, 2009.

Dated: November 16, 2009



Harry Andrew Hild Jr.